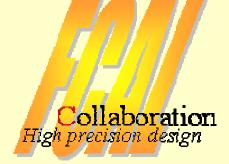
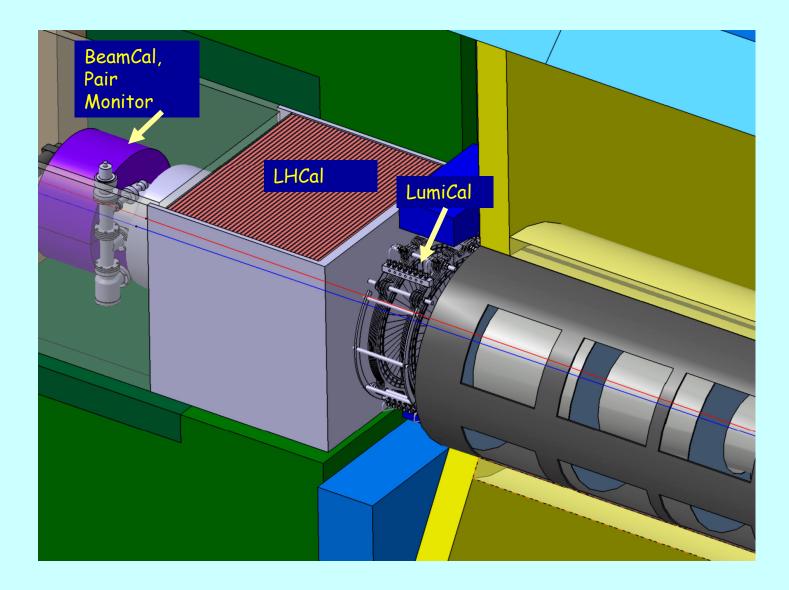
Forward Region Instrumentation





Forward Region, ILD Detector



Content

Recent Developments:

- Sensor Prototyping
- ASIC Development and Test
- -System test
- PITZ test
- Applications of FCAL R&D at FLASH and CMS

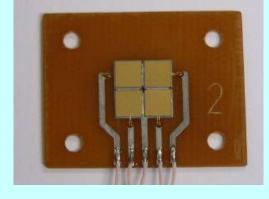
BeamCal Sensors, GaAs

- n-type (Te or Sn shallow donor) GaAs grown by Liquid Encapsulated Czochralski (LEC) method in Siberian Institute of Physics and Technology (Tomsk, Russia) low-ohmic material, filling the electron trapping centers EL2+
- Cr (deep acceptor) diffusion
- -> high-ohmic

Thicknesses 150 - 200 µm

Metallization: V (30 nm) + Au (1 μ m) from both sides

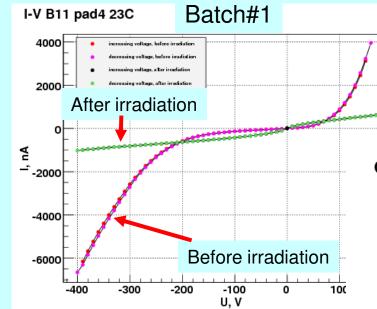
Irradiation in a 10 MeV electron Beam, Doses up to 1.1 MGy



	Initial n-GaAs	Fabrication method
	№1, n ≈ (1 -1.5)*10 ¹⁷ см ⁻³ ,Те	Diffusion of Cr under temperatureT2
	№2, n ≈ (5 - 6)*10 ¹⁶ см ⁻³ , Те	Diffusion of Cr under temperature Tm
	№3, $n \approx (1 - 3) * 10^{16} \text{ cm}^{-3}$, Sn	Diffusion of Cr under temperature T1
1	№4, n ≈ (2 - 5)*10 ¹⁶ см ⁻³ , Те	p-v-n- structure*
Notice T1 < Tm <t2.< td=""><td></td></t2.<>		

* - presence in the detector n- type low-resistance domain, all other detectors N_{21} , 2, 3 had structure m-i-m: metal- insulator (high-resistance GaAs) –metal.

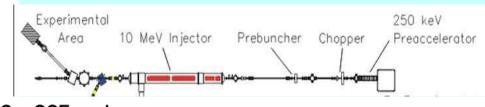
BeamCal Sensors, GaAs



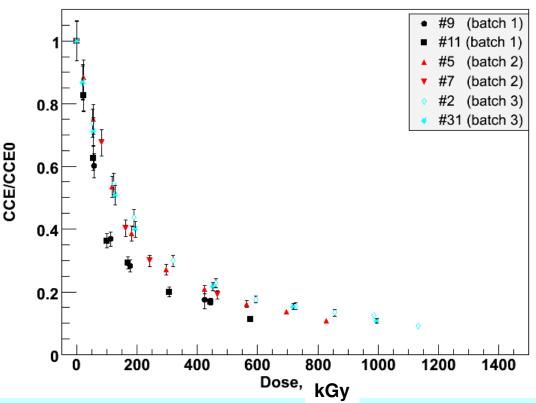
Up to 500 kGy a mip signal is clearly seen

Sensors with a lower concentration of shallow donor and Cr as deep acceptor show better rad. tolerance

Irradiation with an 10 MeV electron beam (DALINAC, TU Darmstadt) 10 - 400 kGy/h



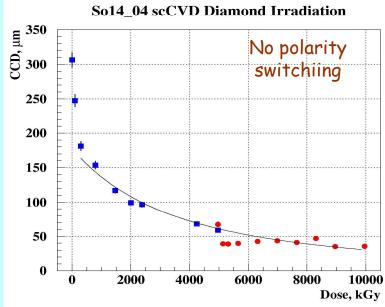
GaAs:Cr CCE vs dose

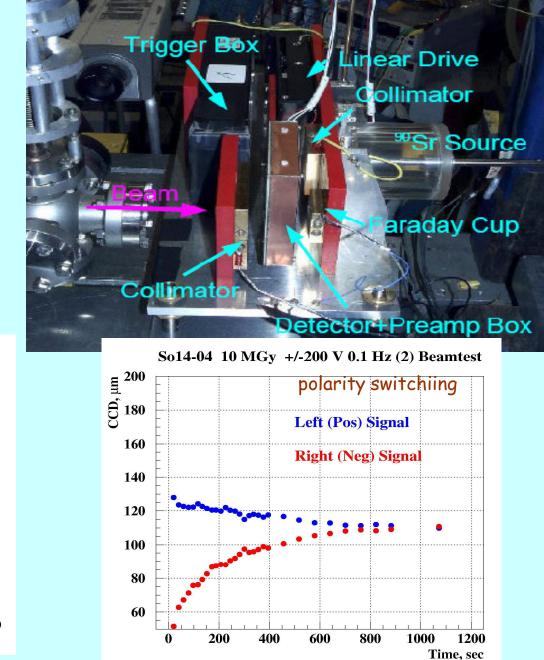


BeamCal Sensors, Diamond

sCVD diamond (E6), 5x5x0.3 mm³ Irradiated in 2007 up to 5 MGy 2008: up to 10 MGy

New set-up, for switching polarity during the measurement



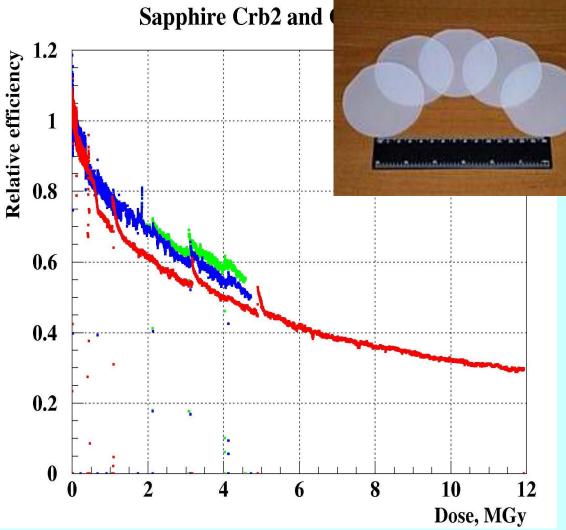


Albuquerque



- Band gap: 9.9 eV
- (diamond: 5.5 eV, Si: 1.12 eV
- Single crystal, 1x1 cm²,
- cut 0001
- Wafer: 30 cm diameter)
- Metallization:
- 50/50/200 nm Al/Ti/Au

Ratio of the detector and Faraday cup currents



Charge collection efficiency: few %

~ 30 % of the initial charge collection efficiiency after 12 MGy

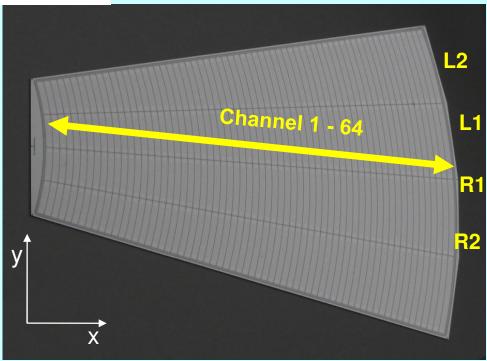
Sensor prototypes (LumiCal)

"Cracow-Design"

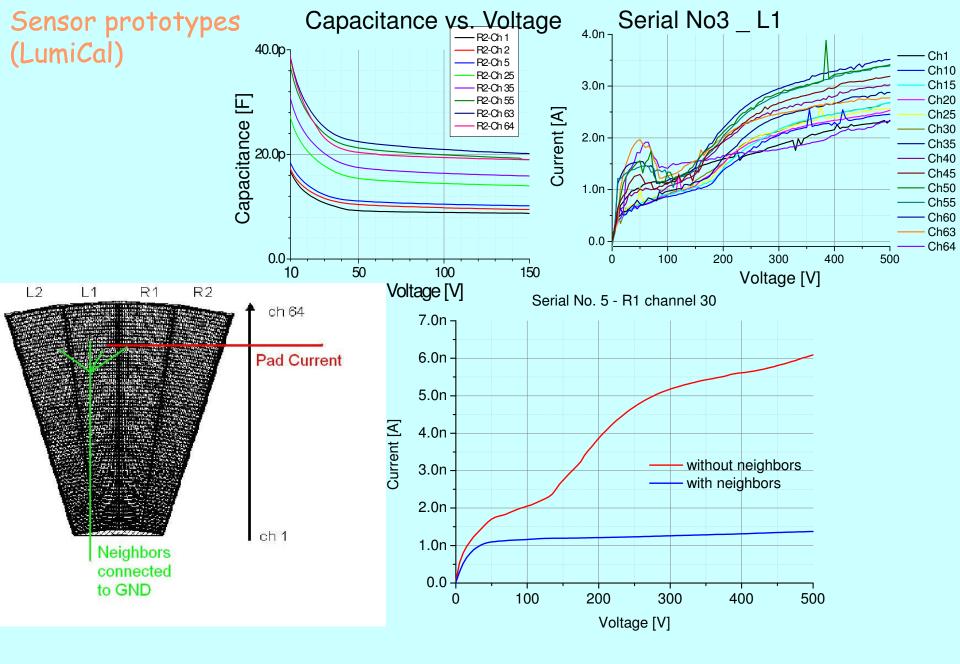
- High resistivity n-type Si
- 1,7mm p+ strips with an Al-metallization
- Backplane: n+ implant and an Al-metallization
- 3 Guard rings

x-Size = 10,8cm y-Size = 4...12cm (6 Inch Wafers)

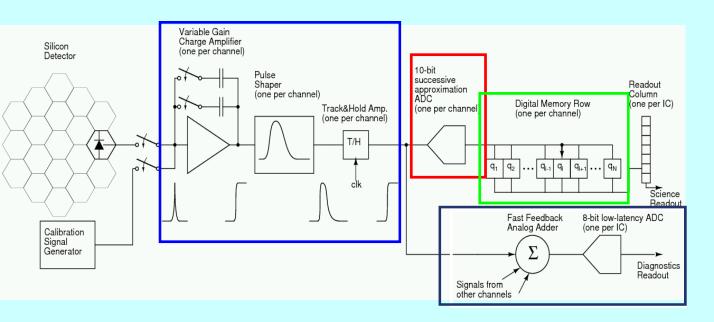
Hamamatsu S10938-8380



I(V) and C(V) measurements on Probestations in Tel Aviv, Cracow and DESY



ASIC development, BeamCal

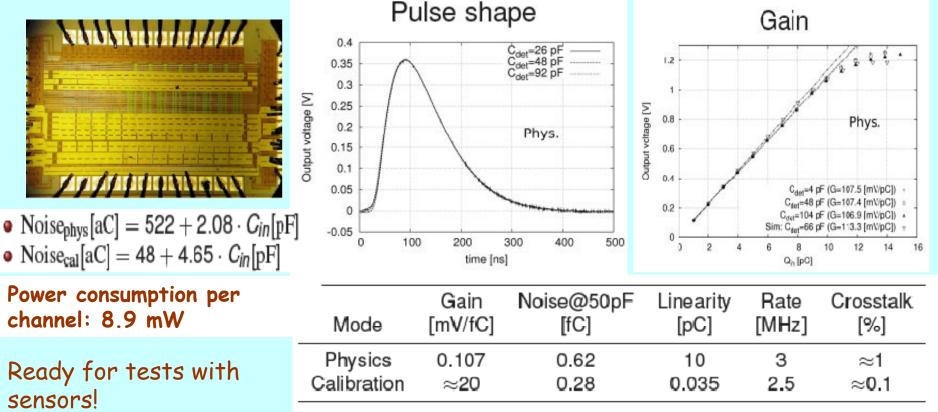


Design of a 32 channel prototype cuurently ongoing, First prototypes (smaller number of channels) will be ready in December

- Dual gain charge amplifier switchched capator filter
- ADC ASIC 10 bit successive approximation ADC (3.25 MS/s)
- Additional 8 bit low latency output (beam diagnostics

ASIC development, LumiCal

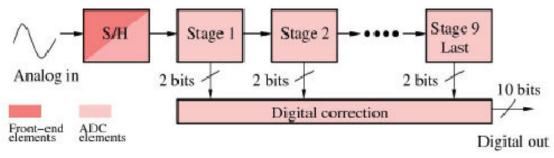
8 channel preamplifier ASIC, lab tests, matches the requirements



- •PCB design for an assembly of ASIC and sensor
- Test in the lab and testbeam
- •Redesign after these tests

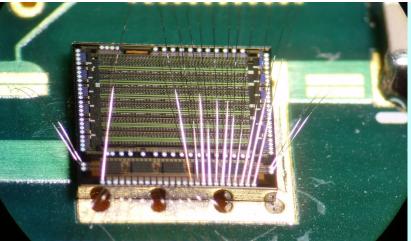
ASIC development, LumiCal

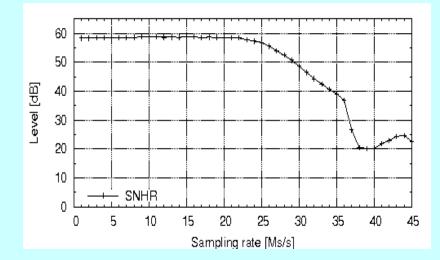
One channel ADC ASIC (differential pipeline architecture)



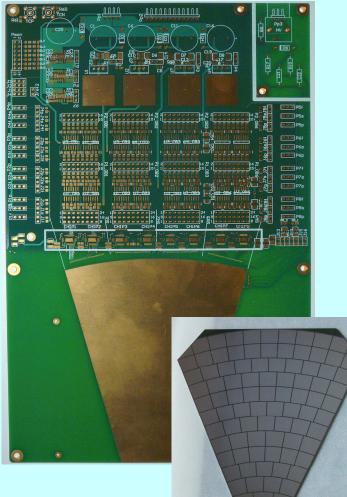


- Stable operation up to 25 MHz
- Good static performance (DNL, INL, ENOB)
- Dynamic measurements just started
- Clock and power switching tests
- Preparation of a multichannel version





System Test in a beam

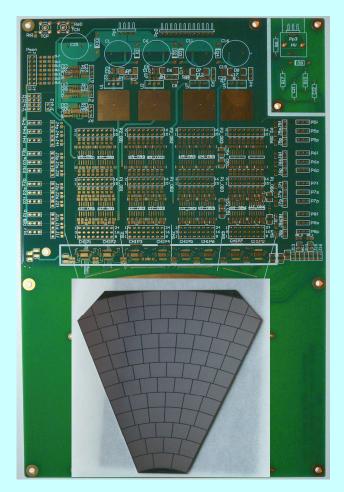


Template of a readout board, to be instrumented with FE ASICS

Readout/Fanout of sensors

- fine pitch PCB, (100...200µm for a few channel FE chips)
- additional flexible PCM to be designed (matters of crosstalk & capacitive load)
- wire bonding or bump bonding to pads (wire bonding needs ~ 3mm gap between absorber tiles; conductive gluing also discussed)
 - wire bonding to FE chip
- Silicon and GaAs sensor samples

System Test in a beam



Template of a readout board, to be instrumented with FE ASICS

Readout/Fanout of sensors

- fine pitch PCB, (100...200µm for current few channel FE chips
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- wire bonding or bump bonding to pads (wire bonding needs ~ 3mm gap between absorber tiles; conductive glueing also discussed)
- wire bonding to FE chip
- Silicon and GaAs sensor samples
- Beam test planned 2010

Test in PITZ

Electron beam, 14 MeV, bunches

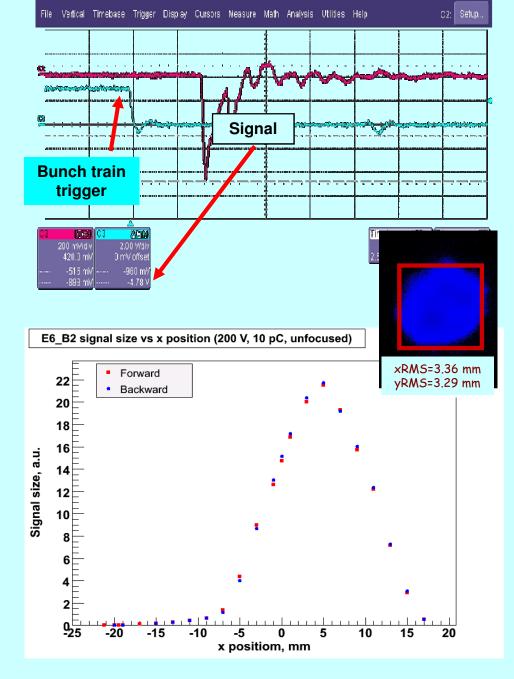
Diamond sensor was installed in the vacuum of the beam pipe



Moving the sensor through an electron beam,

Bunch charge: 1 pC to 1 nC Beam spot: few mm² Beam profile

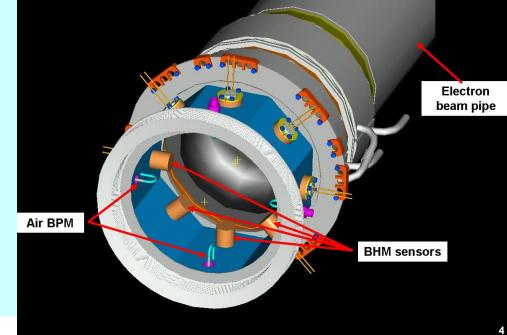
EMI negligible !

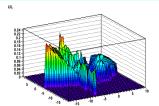


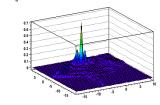
Application at FLASH

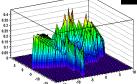
FCAL designed, constructed and installed a Beam-Condition Monitor at FLASH (4 diamond and 4 sapphire sensors) BHM

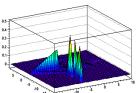
Operation in the "9 mA" run of FLASH was successful



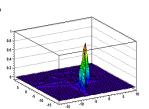


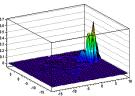


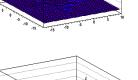












Preliminary

30.09.2009

Albuquerque

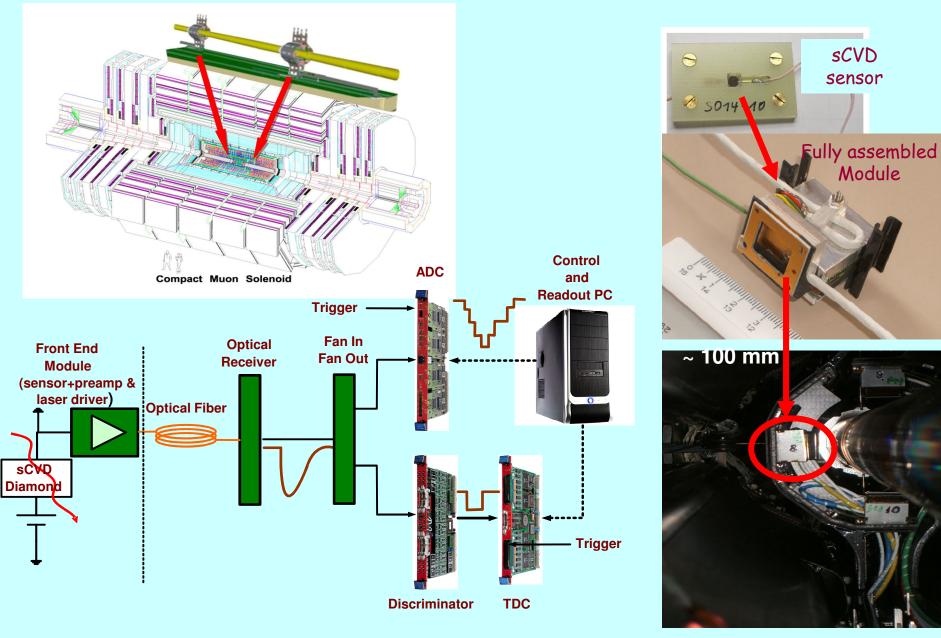
About one week of data taking In September 2009

Analysis ongoing

Preliminary results sweeping the beam

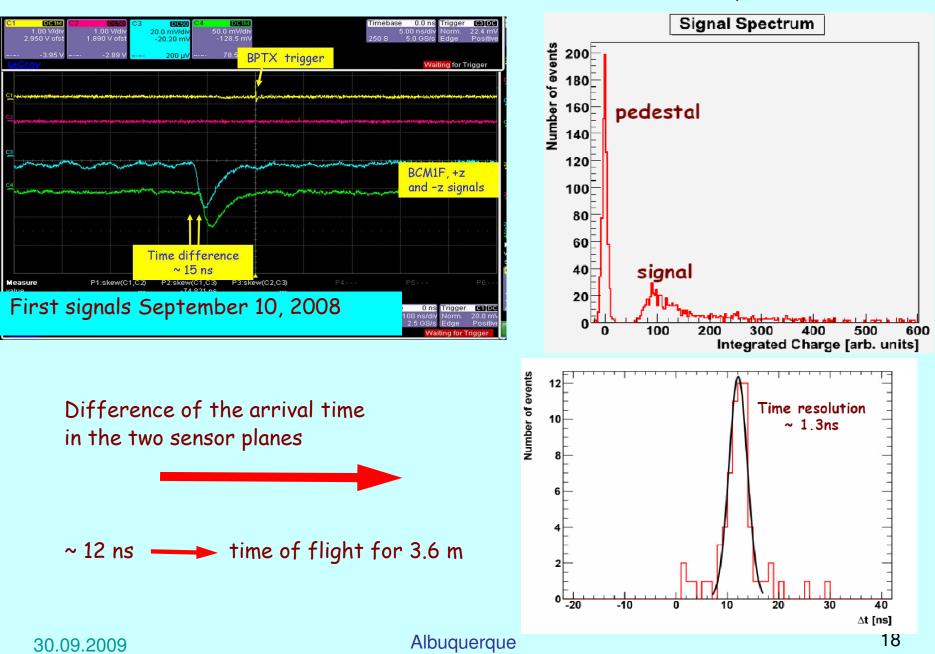


Application at CMS: BCM1F



Application at CMS: BCM1F

Data taken September , 2008



Conclusions

- Investigation of the radiation hardness of GaAs, diamond and Sapphire
 up to 10 MGy. However, no baseline material for BeamCal sensors so far.
- Prototyping of Si sensors for Lumical successful.
- FE ASICS ready for test with sensors.
- System test in preparation.
- ADC ASICS prototypes under test.
- First test of a diamond sensor in a bunched electron beam.
- Successful application of diamond sensors in CMS and FLASH.

Backup

BeamCal Sensors, Diamond

Study of the irradiated sensor in the lab using a $^{90}\text{Sr}\ \beta$ source

